PicoTrack

semi MEMBER

www.picotrack.com

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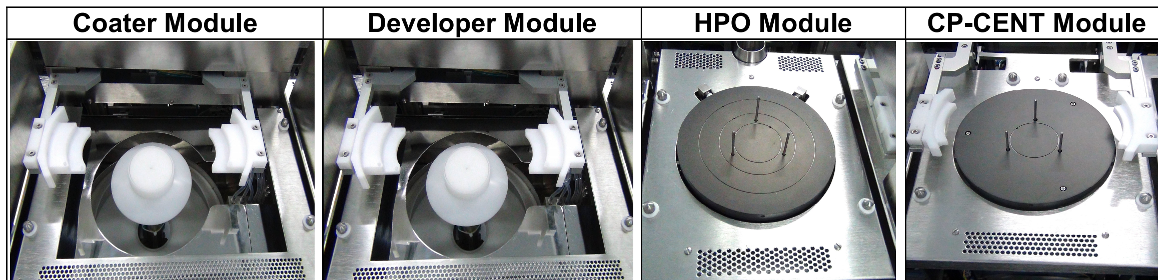
PCT-100RRE TRACK SYSTEM

MASS PRODUCTION WITH DUAL TRACKS (1 COATER, 1 DEVLOPER) TOOL SET

Please contact Sales sales@picotrack.com for more information



<table>
<tr><th>Track System Specification</th><th>Description</th></tr>
<tr><td>System designed</td><td>US Standard System</td></tr>
<tr><td>System Configuration

(*Configuration available upon request)</td><td>
<table>
<tr><td></td><td colspan="5">RANDOM ROBOT ARM # 2</td></tr>
<tr><td>TRACK #2</td><td>SEND</td><td>DEV</td><td>HPO</td><td>CP-CENT</td><td>REC</td></tr>
<tr><td>TRACK #1</td><td>SEND</td><td>COAT</td><td>HPO</td><td>CP-CENT</td><td>REC</td></tr>
<tr><td></td><td colspan="5">RANDOM ROBOT ARM # 1</td></tr>
</table>
</td></tr>
<tr><td>System dimension</td><td>Length: 60” ; Width: 52’’ ; Height: 70’’</td></tr>
<tr><td>Wafer size (workable dual size)</td><td>Up to 4’’ (150mm) or 2’’ & 4’’ auto conversion</td></tr>
<tr><td>Wafer shape</td><td>Round/Square/Rectangular/Triangle/Special</td></tr>
<tr><td>Wafer material</td><td>Silicon/Sapphire/GaAs/ Ceramic…</td></tr>
<tr><td>Wafer sensor</td><td>Optical sensor mapping</td></tr>
<tr><td>System controller</td><td>PC & PLC Controller with Windows OS based</td></tr>
<tr><td>Chemical canister cabinet</td><td>Solvent (EBR, HMDS, Cleaning…), developer liquid</td></tr>
<tr><td>Pumps cabinet</td><td>Photoresist pumps (IDI, Cybor..), dispenser unit, & photoresist bottles</td></tr>
<tr><td>Indexer wafer cassettes capacity</td><td>4 Indexers</td></tr>
<tr><td>Shuttle Robot Arm</td><td>2 Robot arms and dual end effectors</td></tr>
<tr><td>System Fan Filter Unit (FFU)</td><td>Optional</td></tr>
<tr><td>System SECs/GEM</td><td>Optional</td></tr>
<tr><td>Coater</td><td>1 module</td></tr>
<tr><td>Catch Cup Set</td><td>Fixed position</td></tr>
<tr><td>Spindle Unit</td><td>Up/down motion</td></tr>
<tr><td>Maximum spin speed</td><td>6000 rpm</td></tr>
<tr><td>Spin motor type</td><td>Servo</td></tr>
<tr><td>Spin speed accuracy</td><td>± 3 rpm</td></tr>
<tr><td>Acceleration range</td><td>0-50000 rpm/sec</td></tr>
<tr><td>Dispense arm accuracy</td><td>± 0.1 mm</td></tr>
<tr><td>Wafer centering tolerance</td><td>± 0.1 mm</td></tr>
<tr><td>Dispense arm motion control</td><td>Stepper motor and driver</td></tr>
<tr><td>Dispense arm & nozzles</td><td>3x or more (3/16’’ or 1/4’’ OD) (Standard)</td></tr>
<tr><td>Dispense method</td><td>Static and traverse</td></tr>
<tr><td>Pre-dispense function</td><td>Yes</td></tr>
<tr><td>Top/Bottom EBR</td><td>Yes</td></tr>
<tr><td>Catch-cup rinse(CCR)</td><td>Optional</td></tr>
<tr><td>Cleaning tip nozzle</td><td>Optional</td></tr>
<tr><td>Humidity & Temperature control</td><td>Optional</td></tr>
<tr><td>Photoresist temperature control</td><td>Optional (≤ 1°C; 10-50°C range)</td></tr>
<tr><td>Developer</td><td>1 module</td></tr>
<tr><td>Catch Cup Set</td><td>Fixed position</td></tr>
<tr><td>Spindle Unit</td><td>Up/down motion</td></tr>
<tr><td>Maximum spin speed</td><td>6000 rpm</td></tr>
<tr><td>Spin motor type</td><td>Servo</td></tr>
<tr><td>Spin speed accuracy</td><td>± 3 rpm</td></tr>
<tr><td>Acceleration range</td><td>0-50000 rpm/sec</td></tr>
<tr><td>Spin direction</td><td>Clockwise (+) & counter clockwise (-)</td></tr>
<tr><td>Dispense arm motion control</td><td>Stepper motor drive and rotation</td></tr>
<tr><td>Dispense arm accuracy</td><td>± 0.1 mm</td></tr>
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Wafer centering tolerance	± 0.1 mm
Dispense arm nozzles	1 Spray+ 1 Stream or 2 spray+ 2 stream (Standard)
Negative developer nozzles	Cone or fan spray with N2 air assist (Upon request)
Developer dispense type	Stream, Puddle, Fan spray, Cone spray….
Dispense method	Static, traverse and sweep
DI water top and back side rinse	Yes
N2 Air Ring back side	Yes
N2 Blow-off top nozzle	Optional
Developer liquid Temp. controller	Optional (≤ 1°C; 10-50°C range)
Hot Plate Oven (HPO)	**2 modules**
HPO block type	Aluminum anodized with vacuum slots or standoff proximity
Temperature thermal probe	RTD or TC
HPO Temperature controller	Watlow P.I.D with over heating protection
Temperature range	25-250°C, Δt: 50°C ≤ 200s (>250°C option)
Temperature uniformity	± 1°C (25-150°C), ± 2°C (151-250°C)
Wafer carrier	3 pins controlled by stepper motor
Bake method	Contact/ Proximity bake/ or fixed proximity
Chill Plate & Centering (CP-CENT)	**2 modules**
Chill Plate block type	Aluminum anodized with vacuum slots or proximity
Chill Plate Temperature control	House cooling water with flowmeter (18°C to 30°C)
Chill method	Contact
Cooling Water Temperature controller	Optional
Wafer carrier	3 pins controlled by air cylinder
Wafer Centering	Integrated